



Applied Materials' New Ultima Plus System Extends Industry's Leading HDP-CVD Technology

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SANTA CLARA, Calif.--(BUSINESS WIRE)--Sept. 11, 2000--

Enhanced System Features New Remote Plasma Source and cVHP+ Robot

to Significantly Boost Throughput and Lower COO

Applied Materials, Inc. (NASDAQ:AMAT) today announced its new Ultima HDP-CVD(TM) Plus Centura(R) system, a significantly enhanced version of the company's proven, industry-leading Ultima HDP-CVD (high density plasma - chemical vapor deposition) technology. Featuring a new high-efficiency remote plasma source and speedy cVHP+ robot, the Ultima Plus increases system throughput and reduces cost of ownership by more than 20 percent, while offering technology extendibility below

- 0.13 micron. "We have significantly enhanced the performance of our successful Ultima HDP-CVD Centura system to offer high productivity for our customers at a lower operating cost," said Dr. Farhad Moghadam, corporate vice president and general manager of Applied Materials' Dielectric Systems and Modules Product Group. "The Ultima system, which continues to be the preferred gap-fill solution for intermetal dielectric, shallow trench isolation and low k film applications, can now provide even greater value to customers for both 200mm and 300mm applications."

A key feature of the Ultima Plus system is its innovative remote plasma source for chamber cleaning. The source integrates power delivery and ion plasma source technologies to provide a highly efficient reaction with minimal component degradation. The source reduces system clean time and NF3 consumption by more than 40 percent, enabling up to a 10 percent increase in chamber throughput and lower gas cost.

Applied Materials' dual blade cVHP+ robot also contributes to Ultima Plus productivity, providing an additional increase in throughput. The robot's secure wafer capture system boosts rotation speed by 3x for improved sequencing and faster wafer swap time.

Introduced in 1996, Applied Materials' Ultima(TM) system is used by 17 of the top 20 semiconductor manufacturers worldwide for a wide range of applications, including dielectric CVD films related copper device development and production. According to Dataquest and VLSI Research, Applied Materials was ranked the number one supplier of HDP-CVD equipment for two years, 1998-99.

Applied Materials (NASDAQ:AMAT) is a leader of the Information Age and the world's largest supplier of products and services to the global semiconductor industry. Applied Materials' web site is www.appliedmaterials.com.

Note: A Photo is available at URL:

<http://www.businesswire.com/cgi-bin/photo.cgi?pw.091100/bb6>

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